

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1090	349/143	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/18 14:16
L2	1056	349/187	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/18 14:17
L3	1805	349/43	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/18 14:17
L4	4480	pixel with temperature	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/18 14:17
L5	188	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/18 14:27
S1	1151	349/143	US-PGPUB; USPAT; JPO	OR	ON	2005/10/18 14:16
S2	664	349/187	US-PGPUB; USPAT; JPO	OR	ON	2005/10/18 14:17
S3	1050	349/43	US-PGPUB; USPAT; JPO	OR	ON	2005/10/18 14:17
S4	2141	pixel with temperature	US-PGPUB; USPAT; JPO	OR	ON	2005/10/18 14:17
S5	86	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas)	US-PGPUB; USPAT; JPO	OR	ON	2005/10/18 14:18
S6	0	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and (etch\$4 with (weak adj acide))	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:24

S7	0	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and 349/143	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:24
S8	28	(pixel with temperature) and 349/143	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:26
S9	61	(pixel with amorphous) and 349/143	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:26
S10	180	(pixel with amorphous) and 349/43	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:26
S11	107	(pixel with temperature) and (pixel with amorphous)	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 14:24
S12	5558	(pixel and temperature and amorphous)	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:33
S13	3907	(pixel and temperature and amorphous)and (inject\$4 near\$5 (hydrogen with gas))	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:34
S14	768	(pixel and temperature and amorphous)and (inject\$4 near\$5 (hydrogen with gas)) and 349\$.ccls.	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:35
S15	2855	(pixel and temperature and amorphous)and (inject\$4 near\$5 (hydrogen with gas)) and (liquid adj crystal) and substrate	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 13:36
S16	7	(pixel and temperature and amorphous)and (inject\$4 near\$5 (hydrogen with gas)) and (liquid adj crystal) and substrate and (etch\$4 with (weak adj acid))	US-PGPUB; USPAT; JPO	OR	ON	2003/03/06 16:39
S17	111	(pixel with temperature) and (pixel with amorphous)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2003/10/17 17:09
S18	7	(pixel and temperature and amorphous)and (inject\$4 near\$5 (hydrogen with gas)) and (liquid adj crystal) and substrate and (etch\$4 with (weak adj acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2003/03/06 16:41
S19	1	"5135581".pn.	US-PGPUB; USPAT; JPO	OR	ON	2004/02/20 10:48
S20	97	(pixel with amorphous) and 349/43 and temperature	US-PGPUB; USPAT; JPO	OR	ON	2003/03/07 15:29

S21	29	(pixel with amorphous) and 349/187	US-PGPUB; USPAT; JPO	OR	ON	2003/03/07 16:34
S22	62	(pixel with temperature) and 349/43	US-PGPUB; USPAT; JPO	OR	ON	2003/03/07 16:50
S23	27	(pixel with temperature) and 349/187	US-PGPUB; USPAT; JPO	OR	ON	2003/03/07 16:51
S24	54	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4	US-PGPUB; USPAT; JPO	OR	ON	2003/10/17 16:57
S25	7	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas) and etch\$4 and (vacuum adj chamber)	US-PGPUB; USPAT; JPO	OR	ON	2003/10/17 16:59
S26	12	(pixel with temperature) and (pixel with amorphous) and (vacuum adj chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:11
S27	1	"20020085168".pn.	US-PGPUB; USPAT	OR	OFF	2004/02/20 09:07
S28	1	"5135581".pn.	USPAT	OR	OFF	2004/02/20 09:22
S29	1	"6433842".pn.	USPAT	OR	OFF	2004/02/20 09:35
S30	293	349/43 and passivation and (contact adj hole) near10 (drain adj electrode)	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 09:28
S31	287	349/43 and passivation and (contact adj hole) near10 (drain adj electrode)and pixel	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 09:28
S32	245	349/43 and passivation and (contact adj hole) near10 (drain adj electrode)and (pixel near10 (contact adj hole))	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 09:56
S33	0	349/43 and passivation and (contact adj hole) near10 (drain adj electrode)and (pixel near10 (contact adj hole)near10 (vacuum adj chamber))	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 09:59
S34	1	passivation and (contact adj hole) near10 (drain adj electrode)and (pixel near10 (contact adj hole)near10 (vacuum adj chamber))	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 10:00
S35	2	passivation and (contact adj hole) near10 (drain adj electrode)and (pixel near10(vacuum adj chamber))	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 10:13

S36	726	((pixel or conduct\$4) near10 (vacuum adj chamber))and sputter\$4	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 10:23
S37	25	((pixel or conduct\$4) near10 (vacuum adj chamber))and (sputter\$4 near10 hydrogen)	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 11:39
S38	130144	substrate near10 temperature	US-PGPUB; USPAT; JPO	OR	ON	2004/07/14 11:40
S39	34959	(substrate near10 temperature) and sputter\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/14 11:41
S40	4237	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/14 11:41
S41	2358	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/14 11:42
S42	262	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen and (vacuum adj chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 09:25
S43	0	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen and (vacuum adj chamber)and 204-205/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 09:25
S44	0	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen and (vacuum adj chamber)and "205"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 10:02
S45	13	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen and (vacuum adj chamber)and "204"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 09:26
S46	366	204/192.29	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 10:02

S47	605	204/192.35	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 10:02
S48	346	205/223	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 10:02
S49	0	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen and (vacuum adj chamber)and 205/223	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 10:03
S50	1	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen and (vacuum adj chamber)and 204/192.35	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 10:03
S51	4	(substrate near10 temperature) and sputter\$4 and (pixel or conduct\$4) and hydrogen and (vacuum adj chamber)and 204/192.29	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 10:03
S52	393	(passivation or protect\$4) near10 (inorganic or organic) near10 ((silicon adj nitride) or (silicon oxide)or acrylic or polytetrafluoroethylene or benzocyclobutene or fluoropolymer or perfluorocyclobutane)and (ohmic adj contact)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 14:00
S53	70	(passivation or protect\$4) near10 (inorganic or organic) near10 ((silicon adj nitride) or (silicon oxide)or acrylic or polytetrafluoroethylene or benzocyclobutene or fluoropolymer or perfluorocyclobutane)and (ohmic adj contact) and ((source and drain)near10 (Mo Cr Ti Ta MoW MoTa MoNb))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/07/15 14:03
S58	1	(pixel near10 temperature) and (pixel near10 amorphous) and ((vacuum adj chamber) near10 temperature)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:15
S59	2	(substrate near10 temperature) and (pixel near10 amorphous) and ((vacuum adj chamber) near10 temperature)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:15

S60	152	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:20
S61	94	(pixel near10 temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$10 gas)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:20
S62	152	(pixel with temperature) and (pixel with amorphous) and (inject\$4 near\$5 hydroben near\$5 gas)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/14 09:20